

Contents

ABSTRACT(Chinese).....	i
ABSTRACT.....	iii
ACKNOWLEDGEMENT.....	v
CONTENTS.....	vi
TABLE LISTS.....	ix
FIGURE CAPTIONS.....	xi
CHAPTER 1 Introduction	
1.1 Overview of Vacuum Microelectronics.....	1
1.1.1 History of Vacuum Microelectronics.....	1
1.1.2 Theory Background.....	5
1.2 Applications of Vacuum Microelectronic Devices.....	10
1.2.1 Vacuum Microelectronic Devices for Electronic Circuits.....	11
1.2.2 Field Emission Displays.....	12
1.3 Recent Developments of Field Emission Devices for Field Emission Displays.....	15
1.3.1 Cathode Structures and Materials for Field Emission Displays.....	15
1.3.1.A Spindt-type field emitters.....	15
1.3.1.B Si tip field emitters.....	19
1.3.1.C. Carbon and Nano-sized Emitters.....	21
1.4 Motivation.....	23
1.5 Thesis Organization.....	29

CHAPTER 2 Experimental Procedures

2.1 Introduction.....	31
2.2 CNTs Grown Using Multilayer Catalyst Films at Low Temperature.....	33
2.2.1 Forward Arrangement.....	33
2.2.2 CNT Synthesis.....	35
2.3 MIM Triode Structure on Si Substrate.....	43
2.3.1 Structure Fabrication.....	43
2.3.2 CNT Synthesis.....	45
2.4 CNTs Grown on Glass Substrate.....	45
2.4.1 Sample Preparation.....	45
2.4.2 CNT Synthesis.....	46
2.5 Analysis.....	47

CHAPTER 3 Results and Discussion

3.1 CNTs Grown Using Multilayer Catalysts at Low Temperature.....	50
3.1.1 Effect of interlayer (Exp. A).....	50
3.1.2 Effect of heat from formation carbide (Exp. B).....	61
3.1.3 Effects of surface energy (Exp. C).....	73
3.1.4 Effect of Growth Temperature (Exp. D).....	77
3.1.5 Stress test (Exp. E).....	83
3.2 Gated Triode Structure (Exp. F).....	88
3.3 CNT-FED on Glass Substrate for Diode Structure (Exp. G).....	94

CHAPTER 4 Conclusions and Future Prospects

4.1 Conclusions.....	99
4.2 Future Prospects.....	101

References.....103
Vita.....113

